from vacuum ultraviolet to far infrared







### alpha-2.0



For routine measurements of thin film thickness and refractive index, the alpha-2.0 dual rotation ellipsometer is a great solution. Designed for ease-of-use: simply mount a sample, choose the model that matches your film, and press measure.

Specification alpha-2.0	
Wavelength range	400 nm to 1000 nm, 190 wavelengths
Angle of incidence	65°, 70°, 75° or 90° and transmission (manual)
Data acquisition time	5-10 seconds for full spectrum (typically

theta-SE



The theta-SE is a push-button spectroscopic ellipsometer for characterizing thin film uniformity. It features advanced ellipsometry instrumentation in a compact package at an affordable price.

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Specification theta-SE®		
Wavelength range	400 to 1000nm, 190 wavelengths Dual rotating ellipsometer technology	
Angle of incidence	65°	
Data acquisition time	0.3 sec (fastest), 1-2 sec (typical)	
Mapping stage	300 mm theta-theta	
Spot size	~250 µm x 600 µm	

### iSE – In-situ spectroscopic ellipsometer



We are excited to announce a new ellipsometer developed specifically for in-situ monitoring of thickness and optical properties.

Determine thickness and optical constants with high certainty with our proven spectroscopic ellipsometry including advanced data analysis capability, gives you thickness and optical properties with much higher certainty than other techniques.

Specification iSE		
Measurement speed		
Fastest	Complete spectrum in 0.3 seconds	
Typical	Complete spectrum in 1-2 seconds	
Technology	Patented dual-roatation <sup>TM</sup> optics with CCD detection	
Wavelength options		
# of wavelengths	190	
Wavelength range	400 - 1000 nm	
Measurement types	Advanced measurements within 0.3 seconds	
	Fast, accurate measurements with great sensitivity over full range of values	
	Advanced measurements including generatlized SE and Mueller-matrix SE	





#### M-2000®



The M-2000 delivers both speed and accuracy. Our patented RCE technology combines Rotating Compensator Ellipsometry with high-speed CCD detection to collect the entire spectrum (hundreds of wavelengths) in a fraction of a second with a wide array of configurations. The M-2000 is the first ellipsometer to truly excel at everything from in-situ monitoring and process control to large-area uniformity mapping and general purpose thin film characterization.

Specification M-2000	
Wavelength range	
M2000V	370 - 1000 nm, 390 wavelengths
M2000VI	370 - 1690 nm, 580 wavelengths
M2000U	245 - 1000 nm, 470 wavelengths
M2000UI	245 - 1690 nm, 660 wavelengths
M2000X-210	210 - 1000 nm, 485 wavelengths
M2000XI-210	210 - 1690 nm, 675 wavelengths
M2000D	193 - 1000 nm, 500 wavelengths
M2000DI	193 - 1690 nm, 690 wavelengths
Angle of incidence	
Fixed angle	65°
Horizontal auto angle	45° - 90°
Vertical auto angle	20° - 90°
Data acquisition time	typical for full spectrum: 0.5 to 5 sec.
Max. data acquis. rate	20 Hz

#### RC2®



The dual rotating compensator ellipsometers RC2 are new generation of advanced spectroscopic ellipsometry.

Superior measurement accuracy and precision, combining standard ellipsometry with measuring all 16 elements of complete Mueller Matrix.

Fast CCD detection (0.3 sec for entire spectrum even with full MM measurement), automated intensity adjustment for measurements as ex-situ or in-situ system.

Specification RC2®		
Wavelength range		
RC2-U	210 – 1000 nm, ~790 wavelengths	
RC2-X	210 – 1000 nm, ~790 wavelengths	
RC2-D	193 – 1000 nm, ~800 wavelengths	
+1	1005 – 1690 nm, ~275 wavelengths	
+XNIR	1005 – 2500 nm, ~250 wavelengths	
Angle of incidence		
Fixed angle	65°	
Horizontal auto angle	45° – 90°	
Focusing	65°	
Vertical auto angle	20° – 90°	
Data acquisition time	complete spectrum within 0.3 sec, even for advanced data types	





#### **VASE®**



The VASE is our most accurate and versatile ellipsometer for research on all types of materials as semiconductors, dielectrics, polymers, metals, multi-layers, and more. It combines high accuracy and precision with a wide spectral range of 193 to 4000 nm.

Specification VASE®		
Wavelength range		
Single chamber standard	250 - 2500 nm	
Double chamber standard	240 - 2500 nm	
DUV extension	193 nm	
4IR extension	4000 nm	
Angle of incidence (fully automated)	15° - 90° (standard system) Accuracy: 0.01°	
Data acquisition time		
Typical	0.1 to 3 seconds per wavelength, depending on reflectivity of sample.	
High accuracy	Measurements using full AutoRetarder® capability require 20 seconds per wavelength.	

#### **VUV-VASE®**





The VUV-VASE variable angle spectroscopic ellipsometer is the gold standard for optical characterization of lithography thin films. It measures wavelengths from vacuum ultraviolet (VUV) to near infrared (NIR). This provides incredible versatility to characterize numerous materials.

Specification VUV-VASE®		
Wavelength range	NIR:	146 nm to 1100 nm, 146 nm to 1700 nm, 146 nm to 2500 nm
Angle of incidence		
GEN-I	10° - 90°	Wavelengths <300 nm
	25° - 90°	Wavelengths >300 nm
GEN-II	10° - 90°	Wavelengths <300 nm
	20° - 90°	Wavelengths >300 nm
Data acquisition time		
Typical	1 to 3 seconds per wavelength, depending on reflectivity of sample.	
High accuracy	20 - 30 seconds	

#### IR-VASE®

The IR-VASE is the first and only spectroscopic ellipsometer to combine the chemical sensitivity of FTIR spectroscopy with thin film sensitivity of spectroscopic ellipsometry.



It is used to characterize both thin films and bulk materials in research and industry.

Specification IR-VASE®		
Wavelength range	1.7 µm to 30 µm (333 cm <sup>-1</sup> to 5900 cm <sup>-1</sup> )	
Angle of incidence	32° to 90° (standard)	
Data acquisition time	1 to 30 minutes typical (1 angle of incidence at 16 cm <sup>-1</sup> resolution). Finer resolution will require longer time.	



